

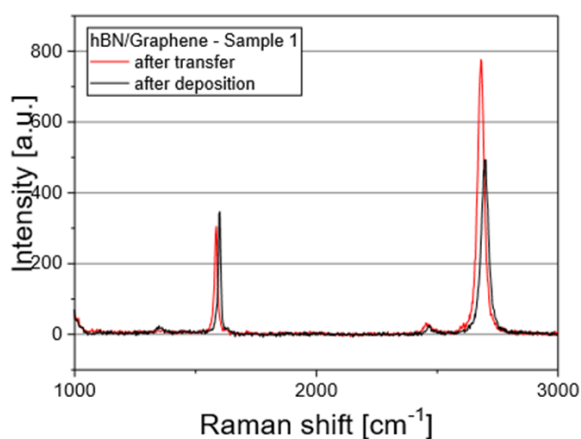
## Summary File:

### **Title: Low Damage Remote Plasma ALD of Dielectric Layers on Graphene**

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## Figures:



**Figure 1:** Raman spectra displaying Raman band structure for pristine graphene (red line) and post deposition 10 nm of Al<sub>2</sub>O<sub>3</sub> (black line). As shown, there is no evidence for damage/defects to graphene as suggested by a D peak intensity below noise level. The ratio between the bands at ca. 2700 and 1600 cm<sup>-1</sup> also suggest high quality graphene has been maintained post-deposition of alumina.

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